



Atty. Docket

US 010610

Group Art Unit: 2822

Examiner: M. LEWIS

Title: DUAL GATE OXIDE HIGH-VOLTAGE SEMICONDUCTOR DEVICE

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

METHOD FOR FORMING THE SAME

Commissioner for Patents Washington, D.C. 20231

In re Application of .

Serial No. 10/015,847

Filed: DECEMBER 10, 2001

MARK SIMPSON ET AL

AMENDMENT

Sir:

In response to the official Office Action dated October 21, 2002, please amend the above-identified application as follows:

IN THE CLAIMS

Kindly cancel Claims 13-20 without prejudice.

REMARKS

In the outstanding Official Action, restriction was required as between Claims 1-12, drawn to a dual gate oxide high voltage semiconductor and Claims 13-20, drawn to a method for forming a dual gate oxide high voltage semiconductor.

In response, Applicants hereby elect. Claims 1-12 for an examination on the merits, without prejudice to Applicants'